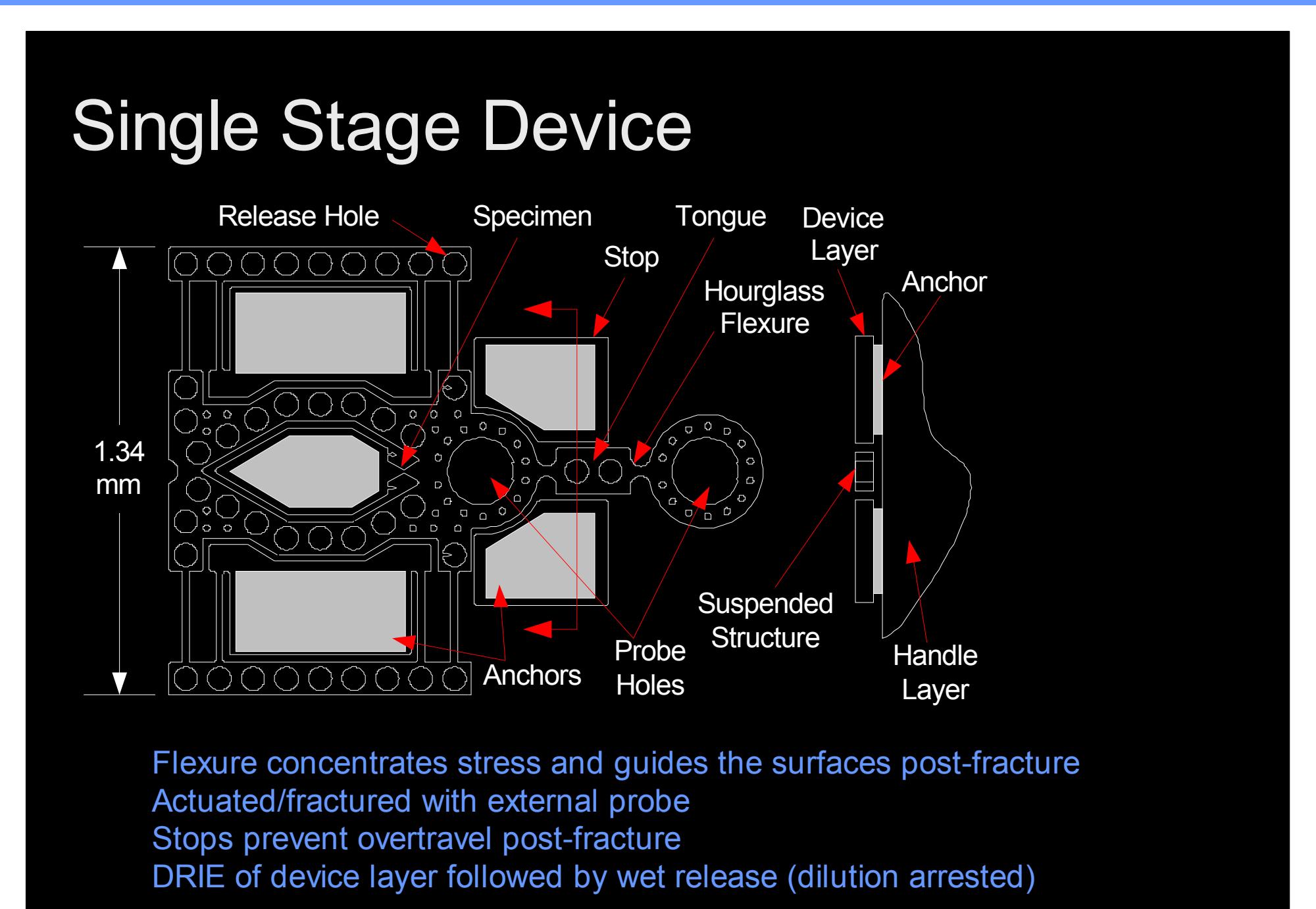


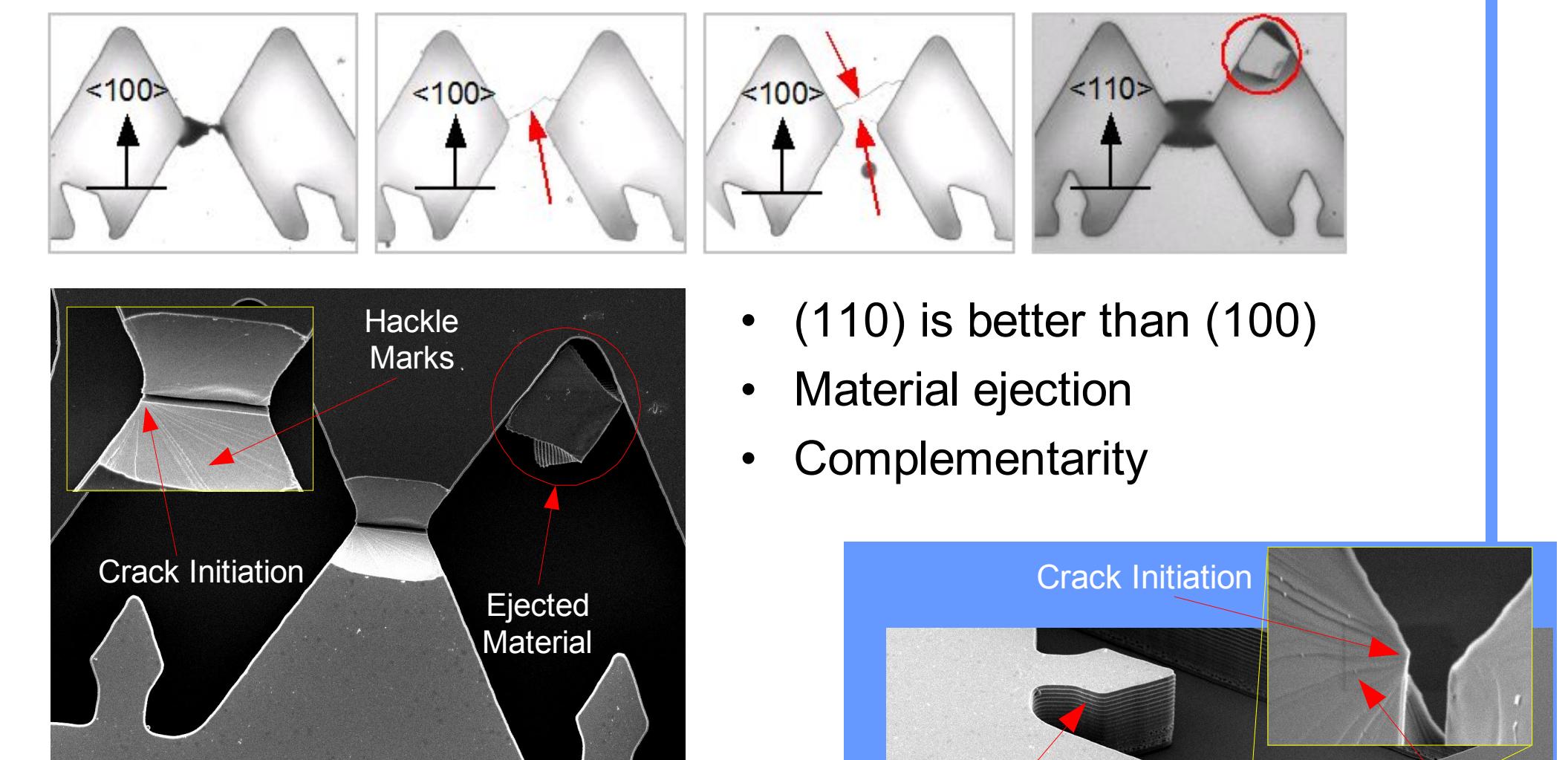
FractureGate: Fracture Fabrication of Single Crystal Silicon Nanosurfaces

MIT Mechanical Engineering – Precision Engineering Research Group
Room 3-470, 77 Massachusetts Avenue, Cambridge, MA 02139
(617) 253-1953, fax: (617) 258-6427

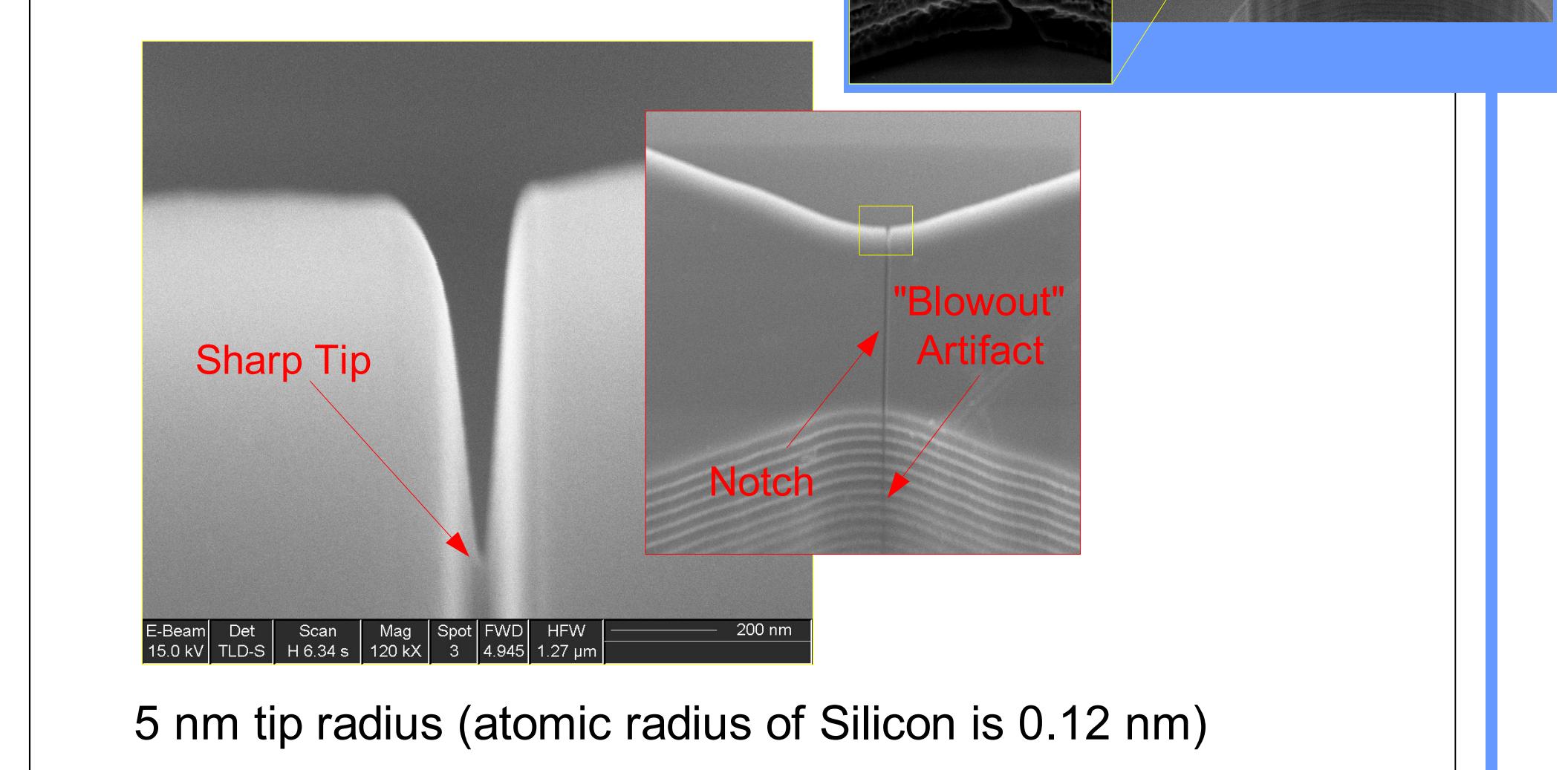
Alexander D. Sprunt & Alexander H. Slocum
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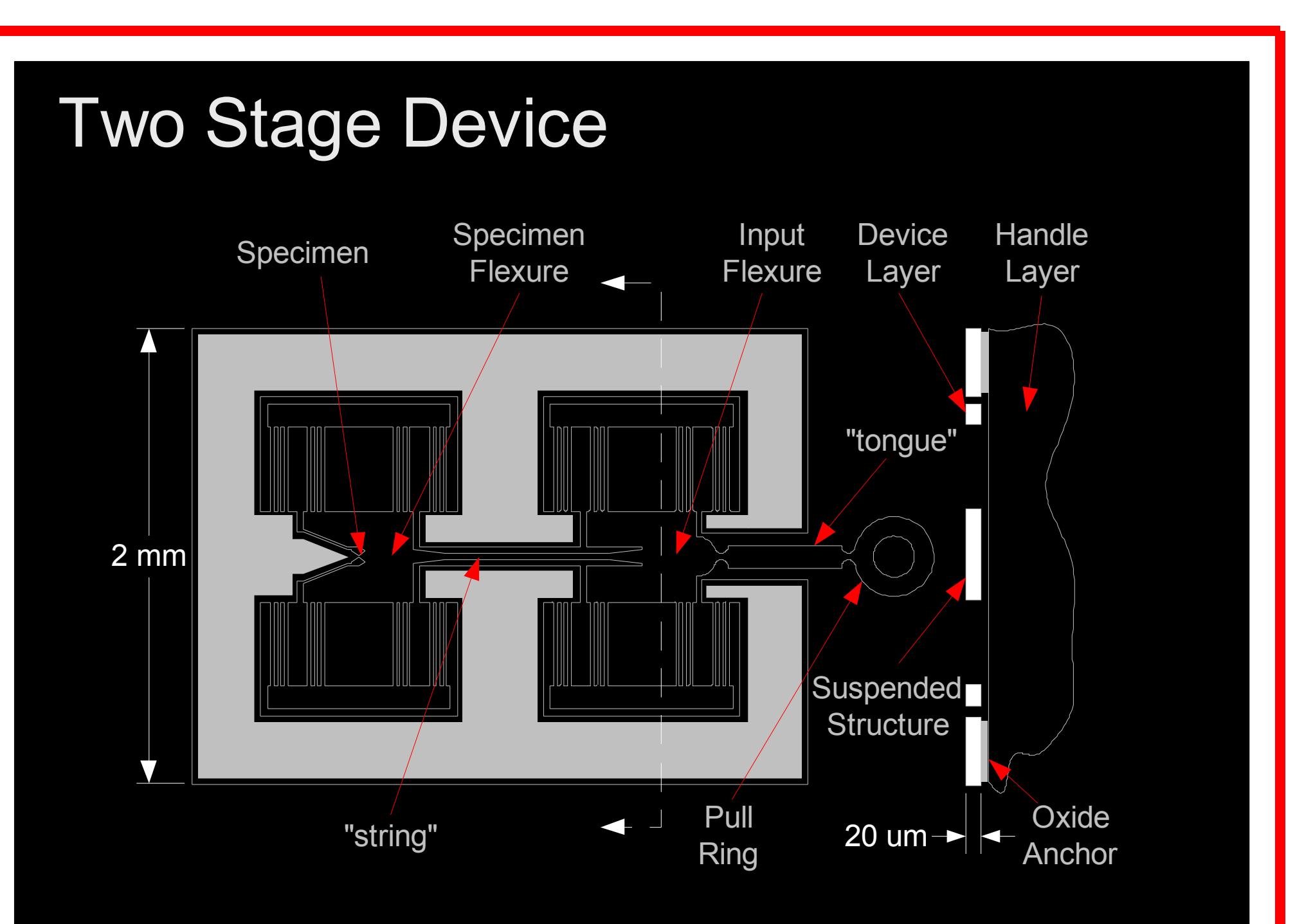
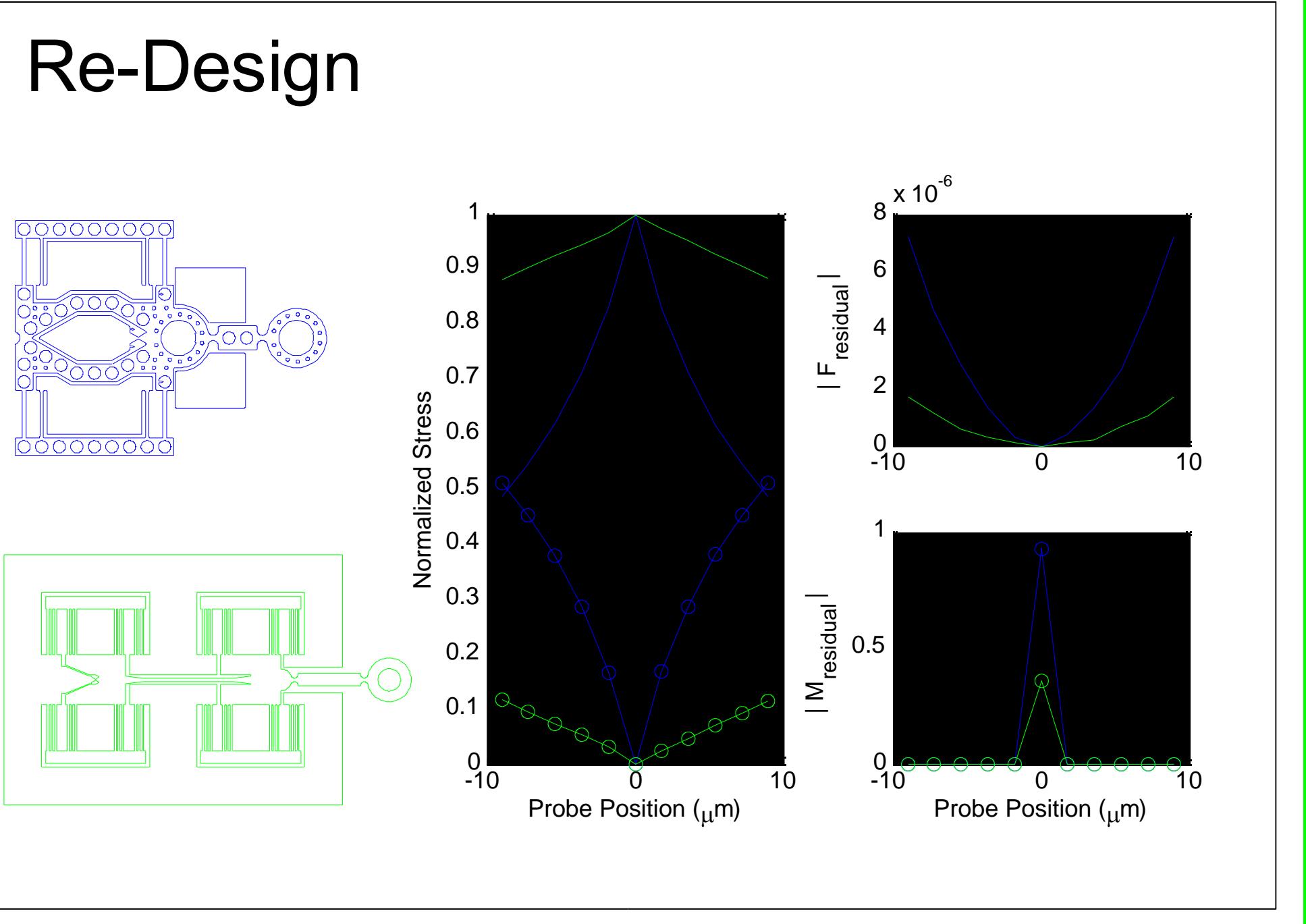
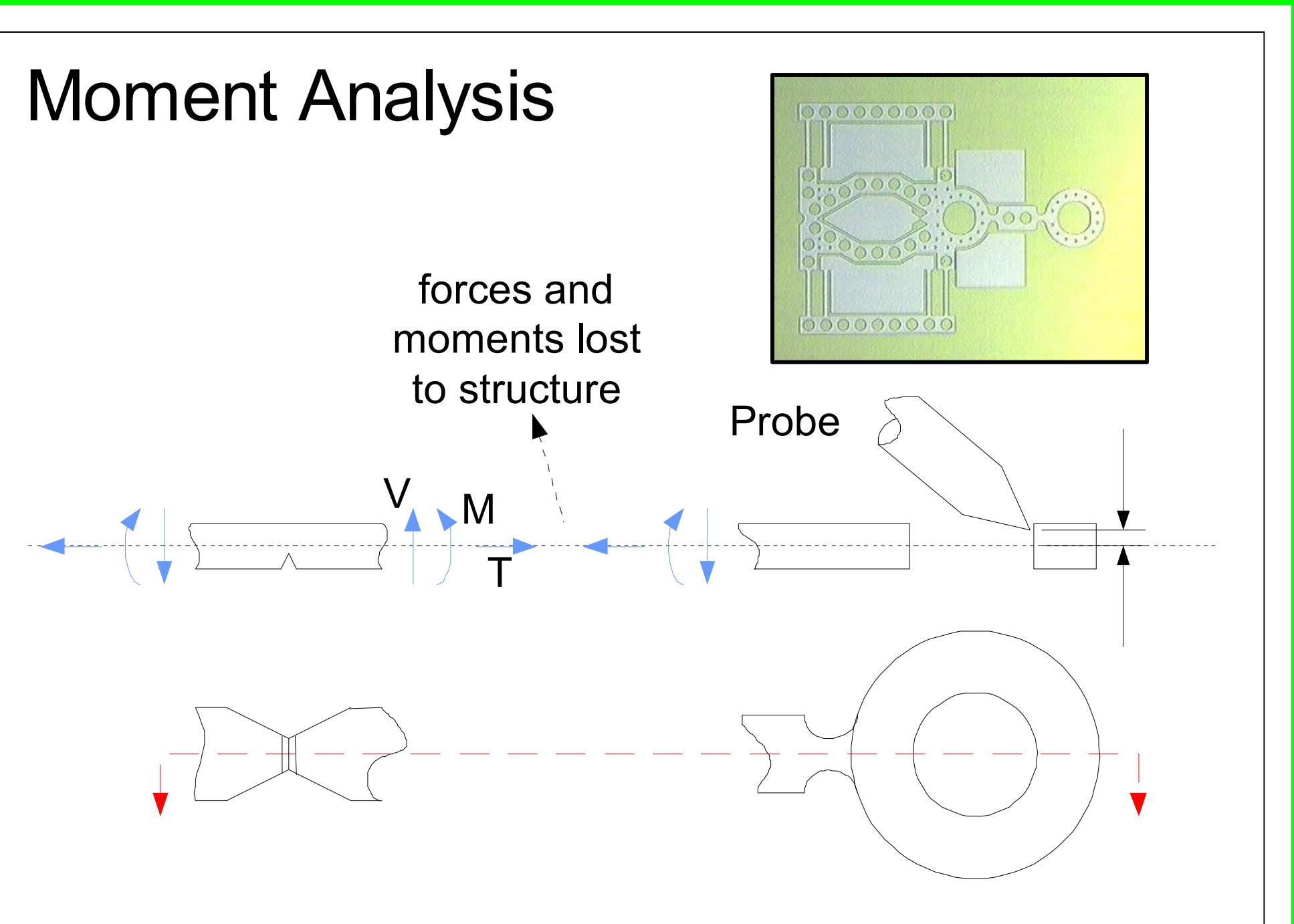
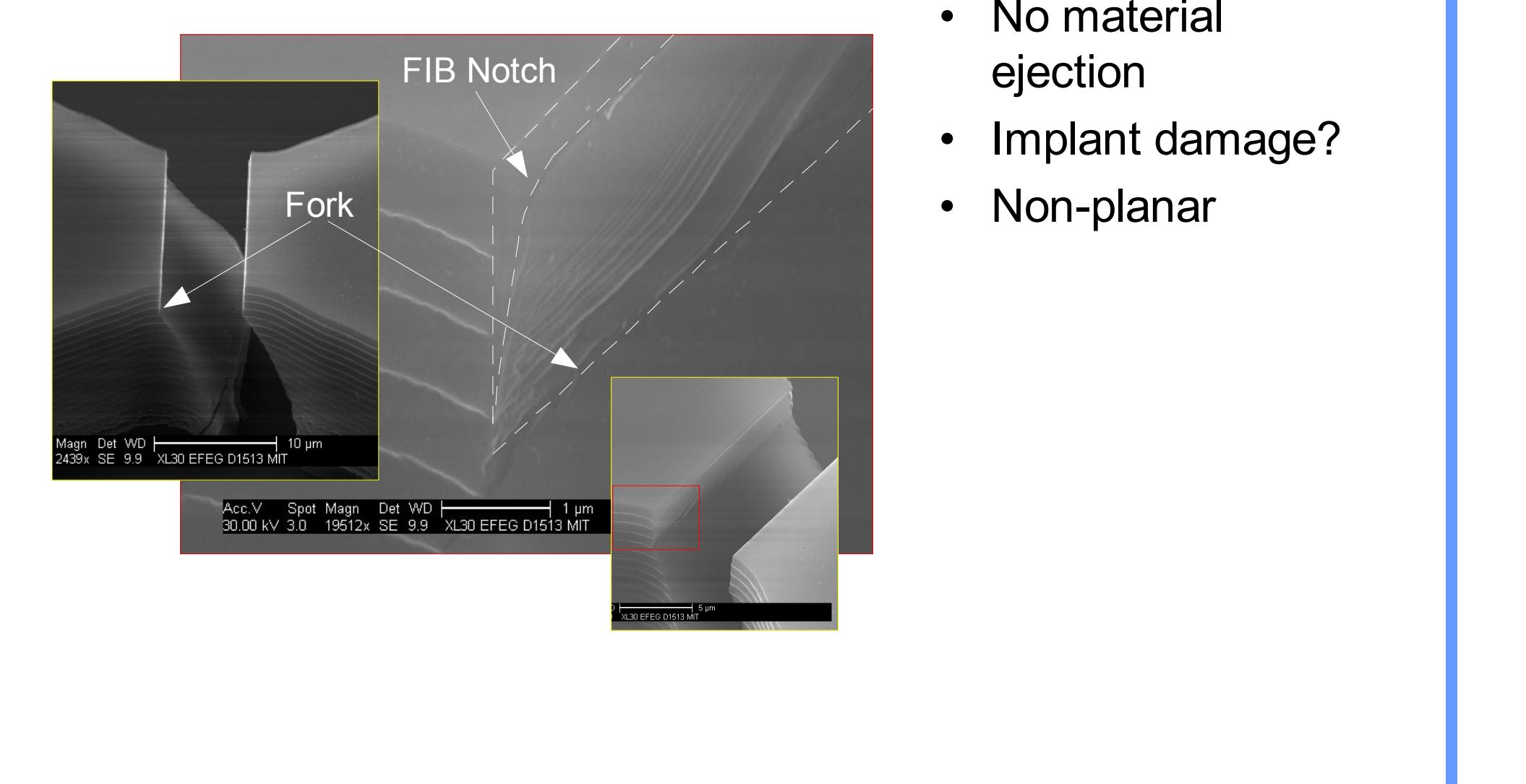
Un-notched Specimens



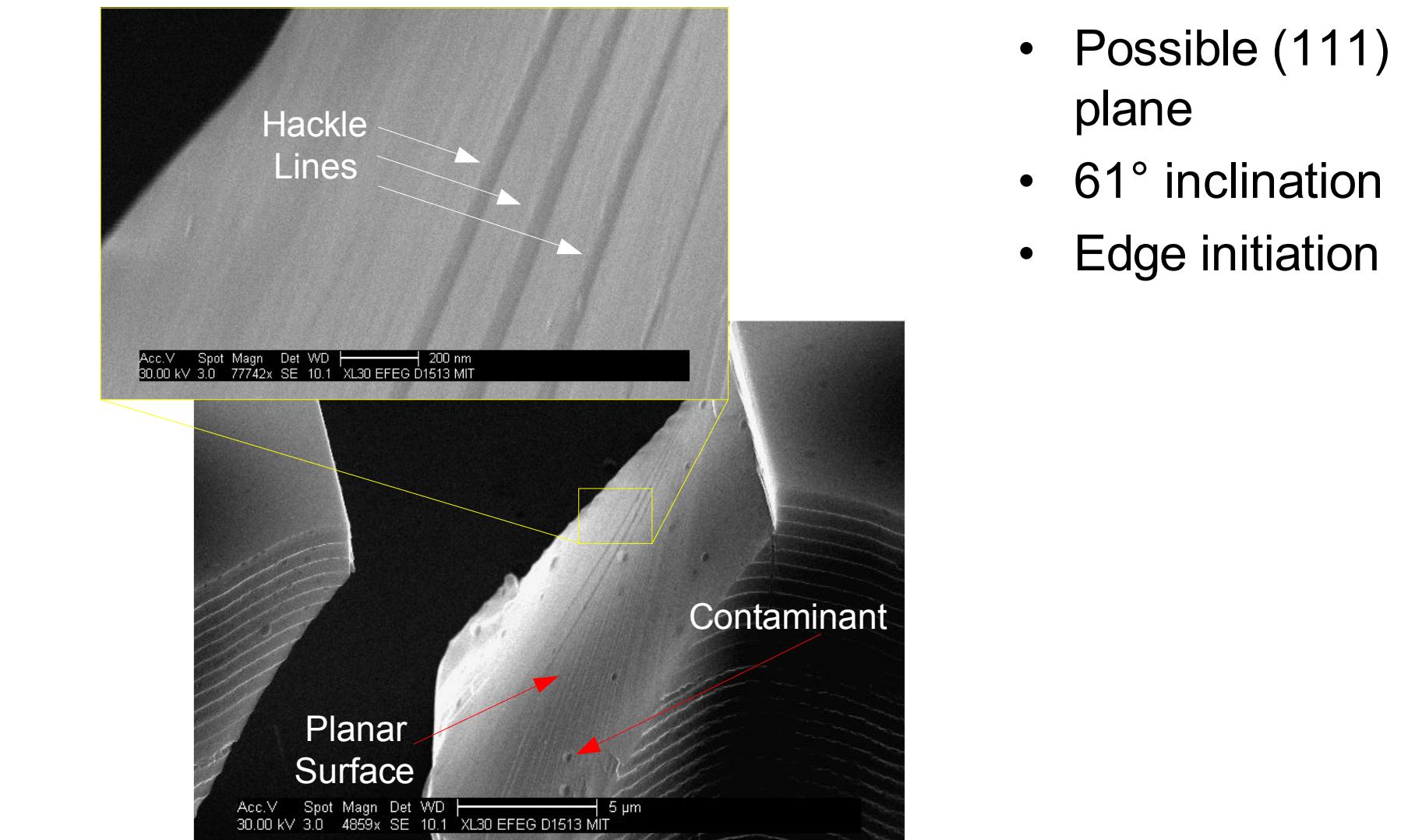
FIB Notch



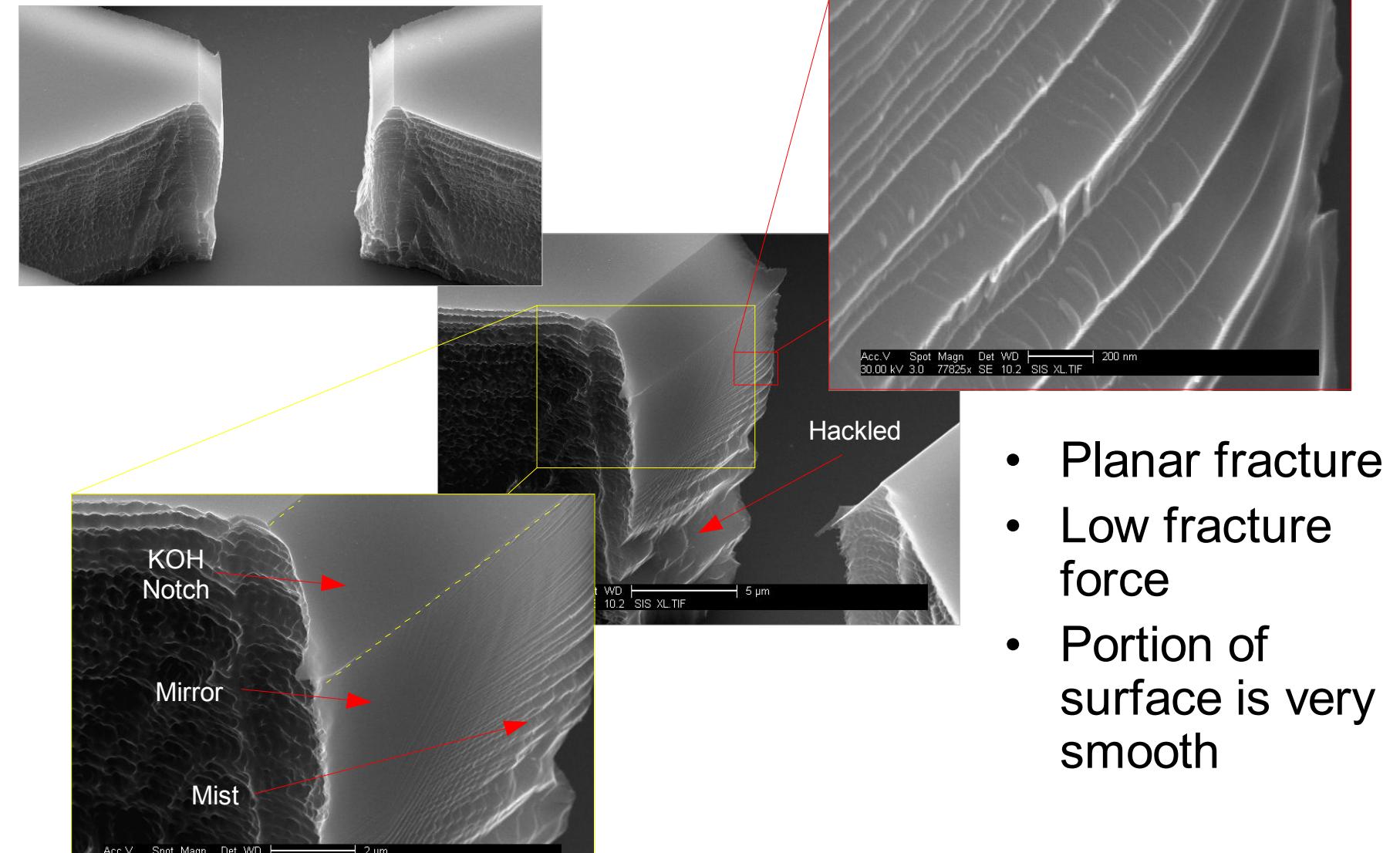
FIB Notched Specimen



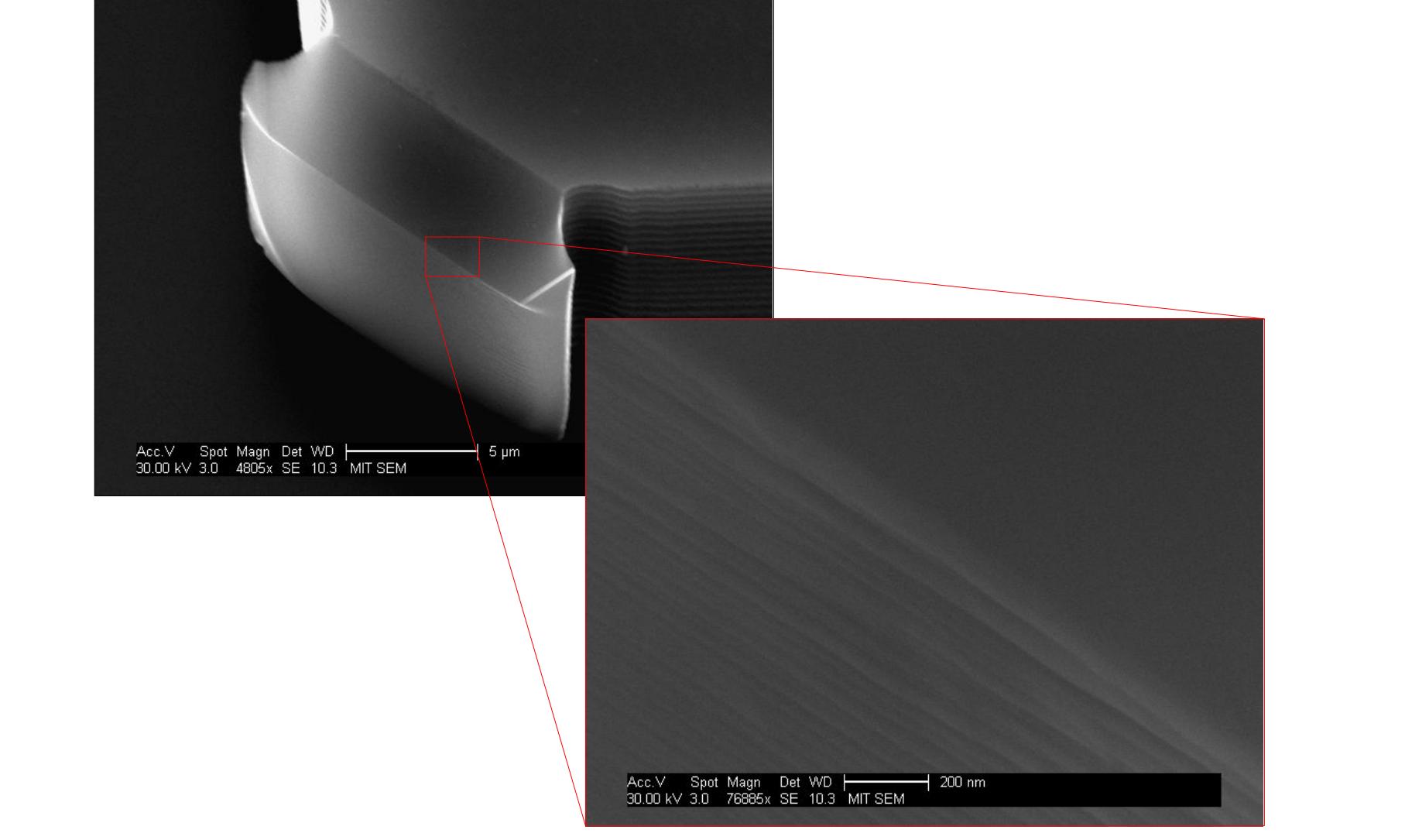
FIB Notch



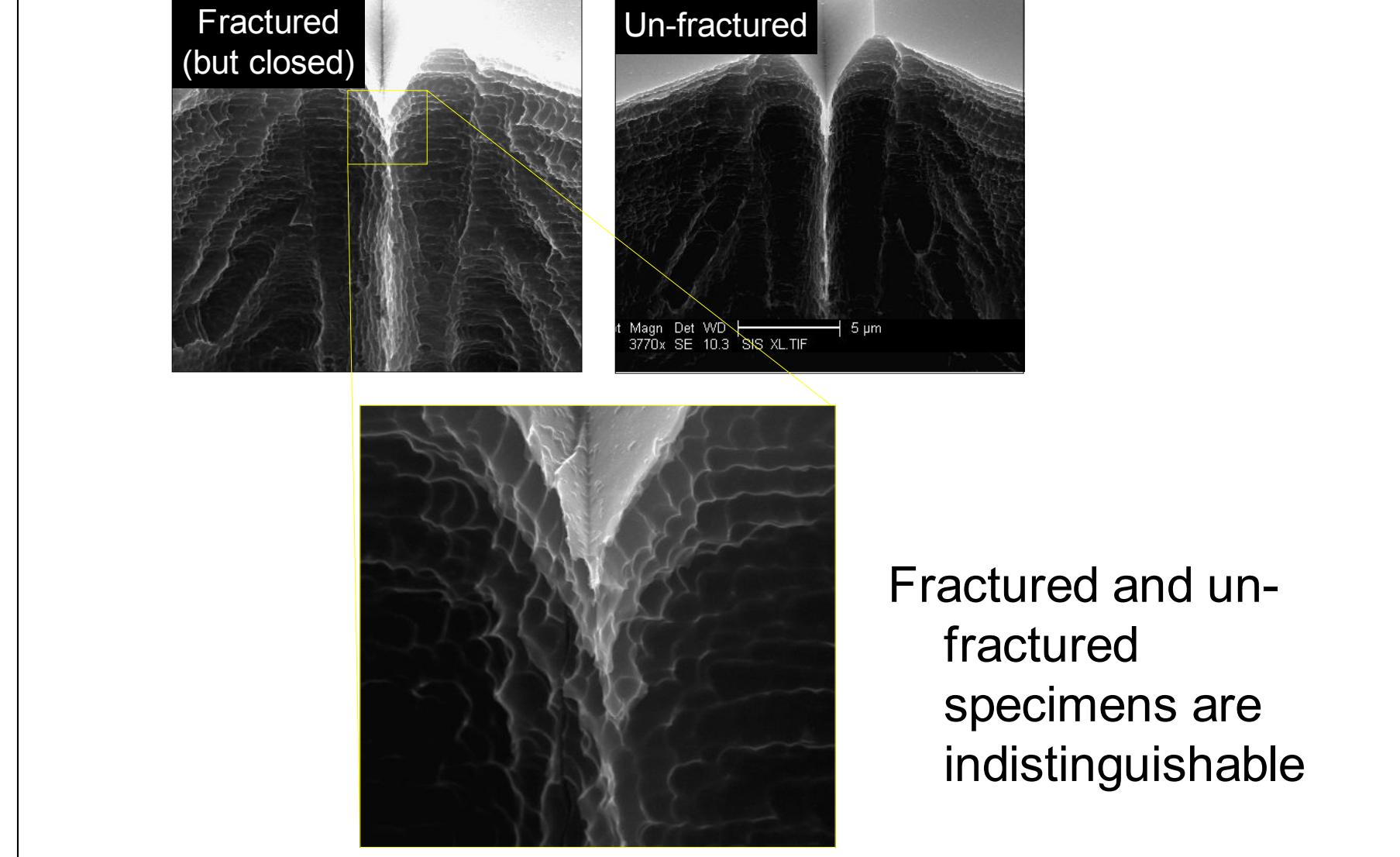
KOH Notch, 20 μm Device Layer



KOH Notch, 10 μm Device Layer

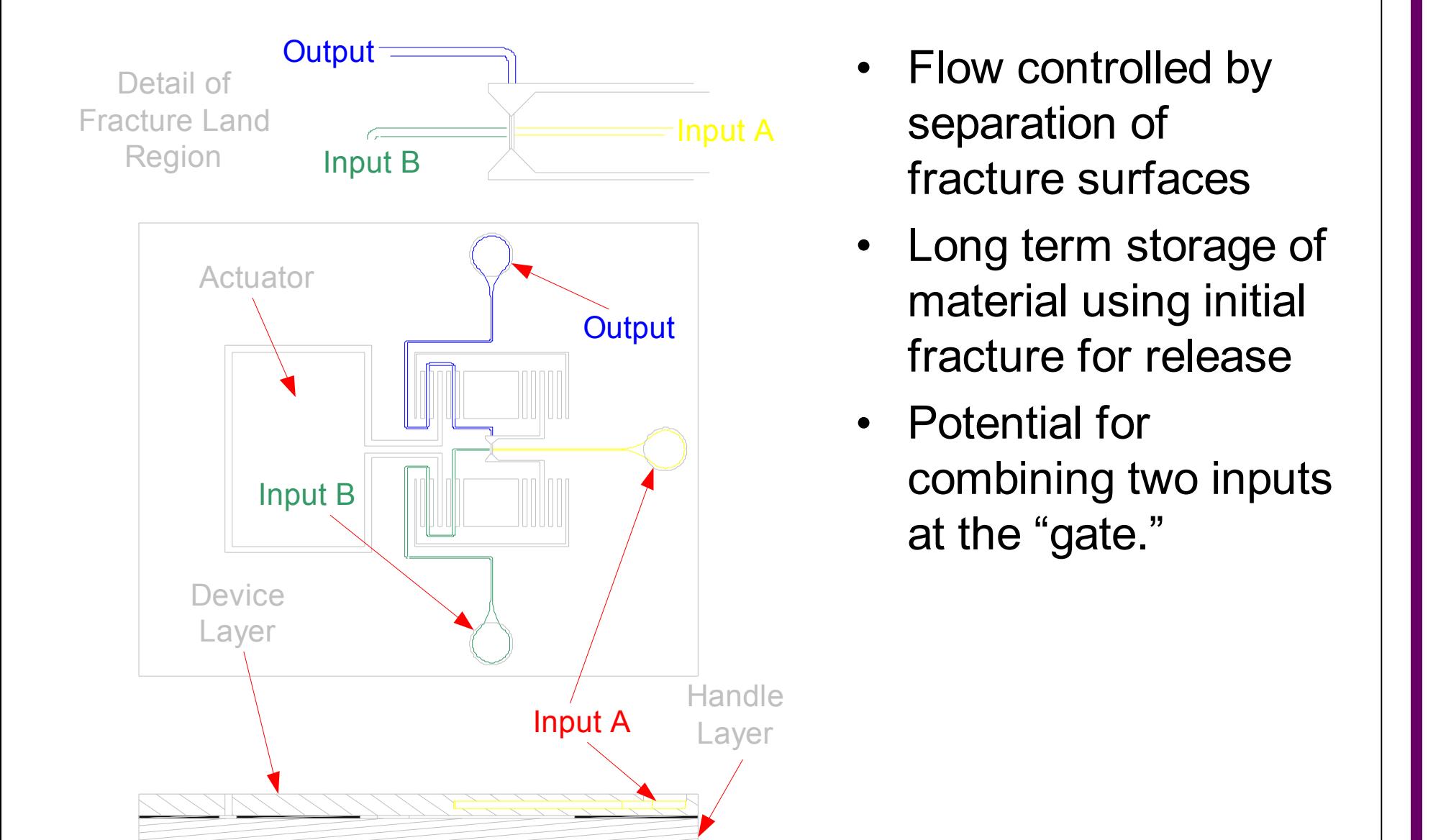
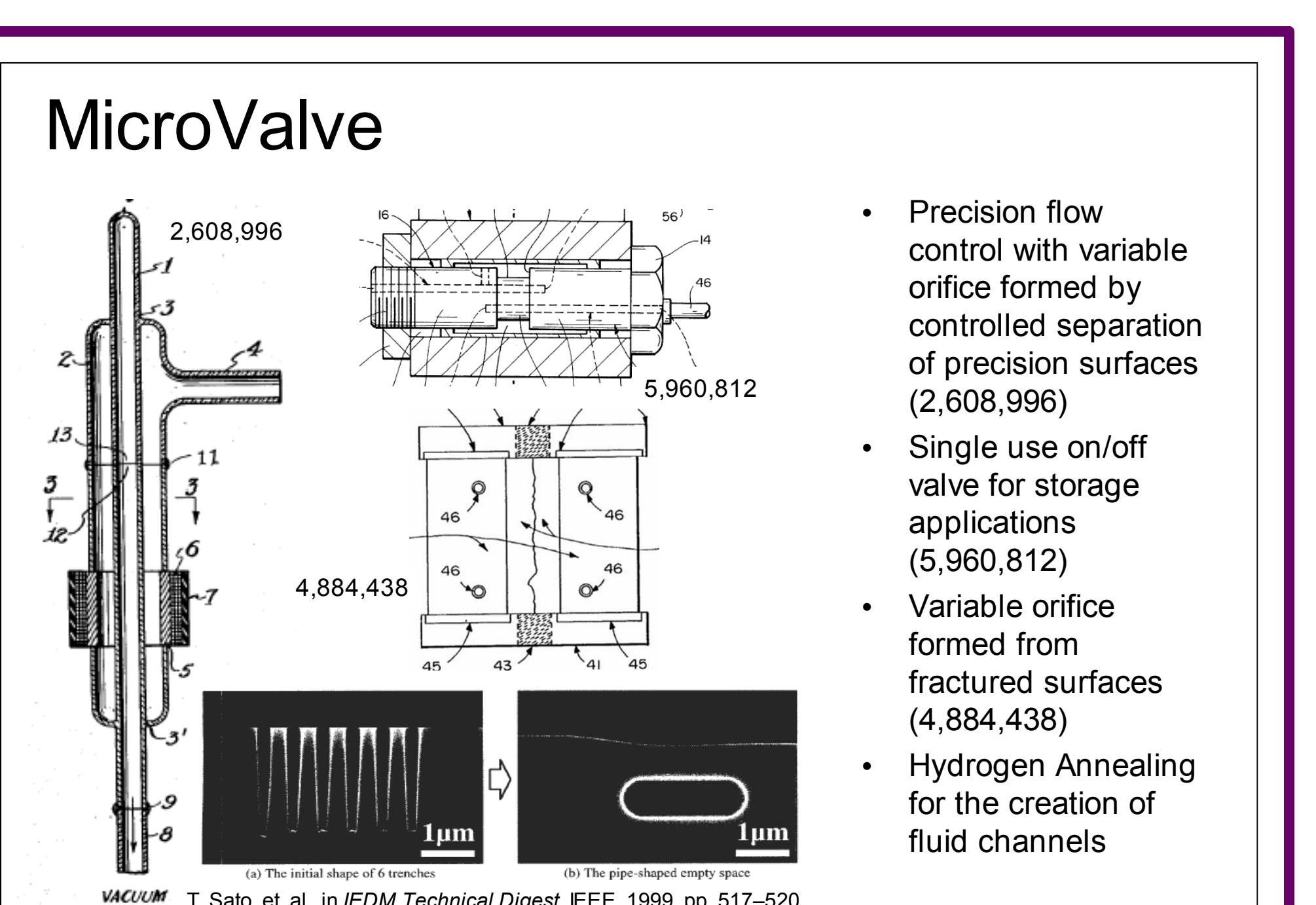


KOH Complementarity

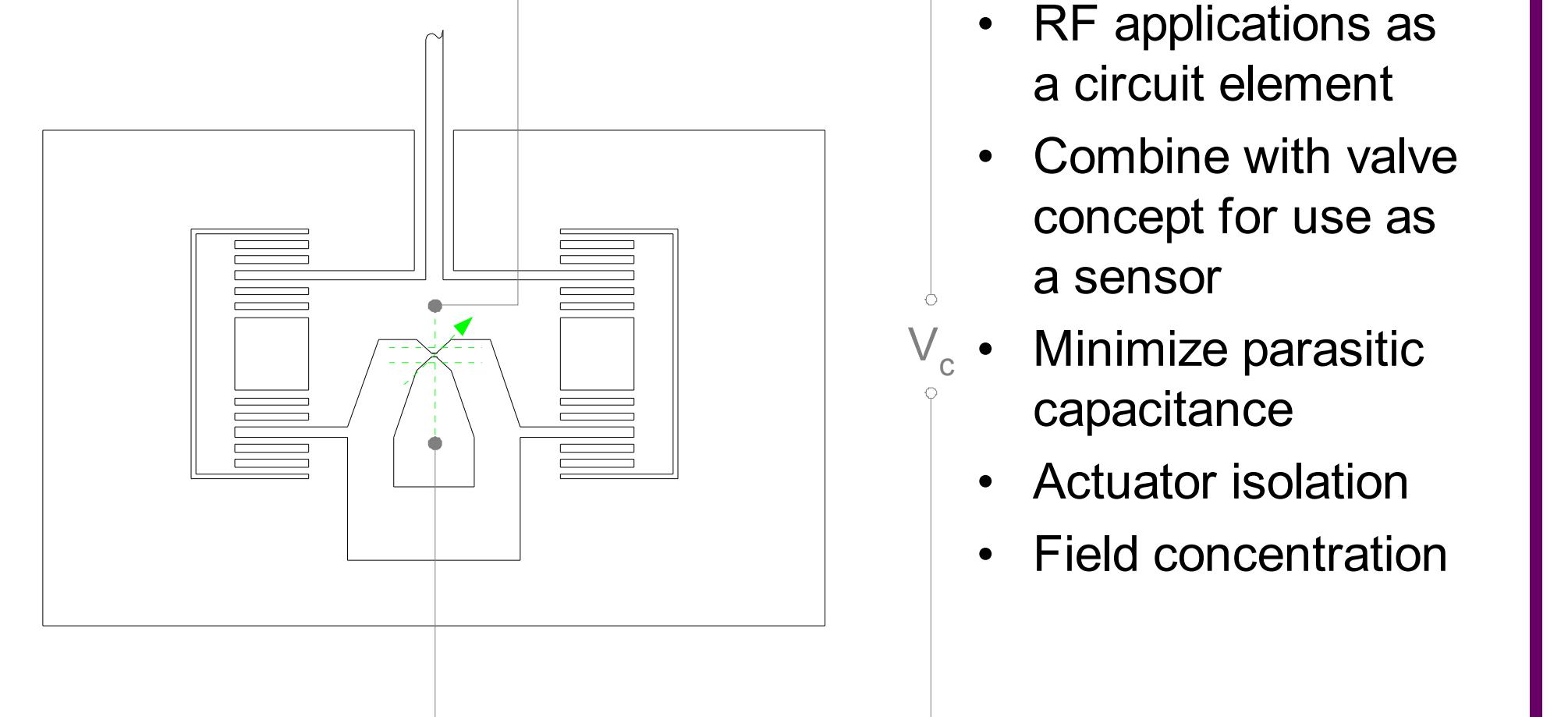


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- MIT Media Lab: Molecular Machines Group
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Variable Capacitor



Physics-in-Gap

